

# **Panel Level Package: Reliability evaluation of double-sided direct copper plated interconnects on embedded power chips by thermal and electrical stress test**

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# Outline

1. Background
2. Our Previous Technical Developments
3. Newly Updated Our Technical Developments
  - Power Cycling Tests for direct Cu plated interconnect
    - Prototyping
    - Power cycling test
4. Summary

# Background

## ■ Applications : Power Supply Systems



Source : NTT Corporation



Source : TOYOTA corporation

- ✓ Recently, with the growth of various power-consuming devices such as motors, Inverters and data center servers, the amount of electricity consumed is increasing year by year.
- ✓ Power systems for AI data centers are moving toward vertical power architectures that increasingly require reduced wiring resistance and inductance.
- ✓ Placing the power supply near the processor (CPU/GPU/HBM) will be an important for power integrity.
- ✓ Chip-embedded packages (3D-like) can shrink size and increase current density.
- ✓ And, the use of wide bandgap power semiconductors such as GaN and SiC devices is also very effective in reducing switching losses, improving heat dissipation, and miniaturizing passive components.

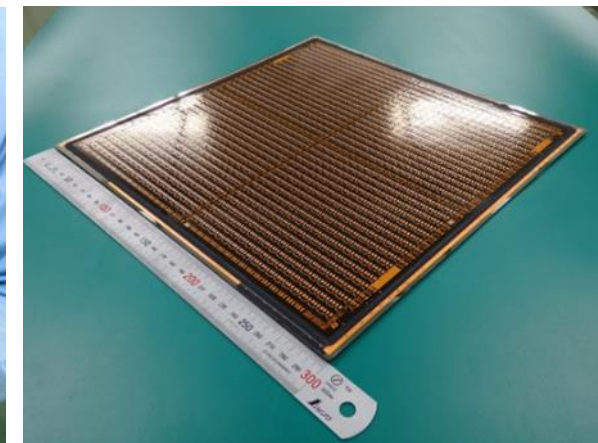
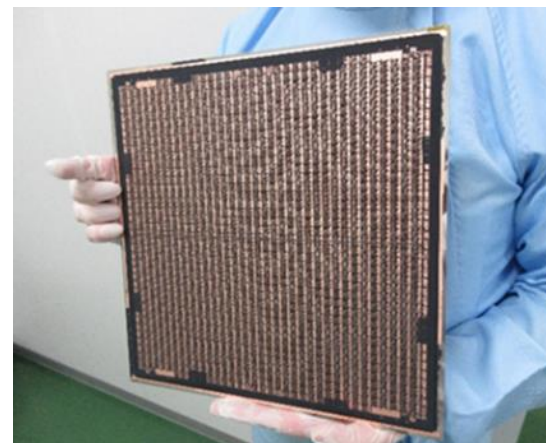
# Previous Technical Developments

## ■ Power Module Packaging Technologies

We focus on power module packages using chip-embedded technology in a panel-level process

Benefits of chip embedded for power module

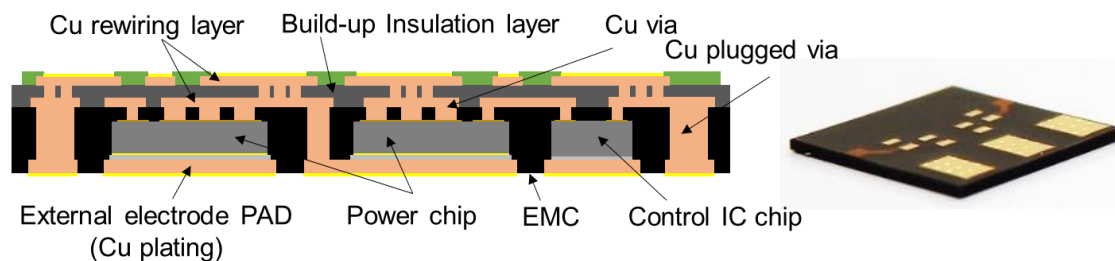
- Higher power (current) density
- Low parasitic resistance and inductance
- Miniaturization and Thinner
- Excellent double-sided cooling concept
- Robust all Cu plated interconnection technology
- Higher scalable integration



## Previous Presentations

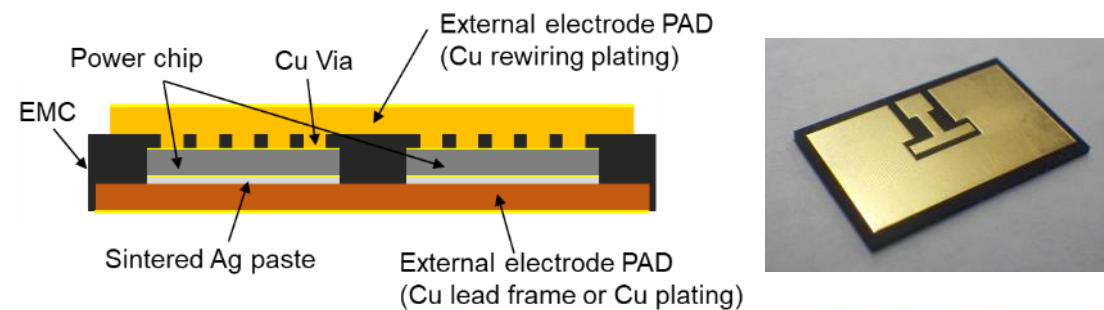
### ✓ IMAPS DPC2023

DC-DC half-bridge application (GaN HEMT module)



### ✓ IMAPS DPC2024 and IMAPS power electronics 2024

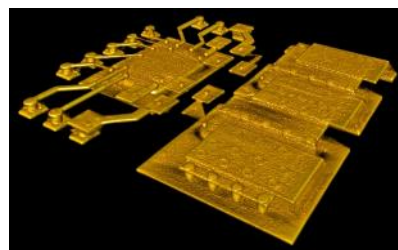
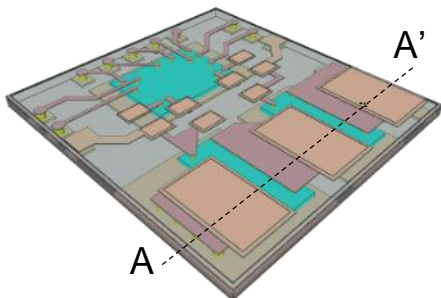
Inverter application (SiC core module)



# Previous Technical Developments

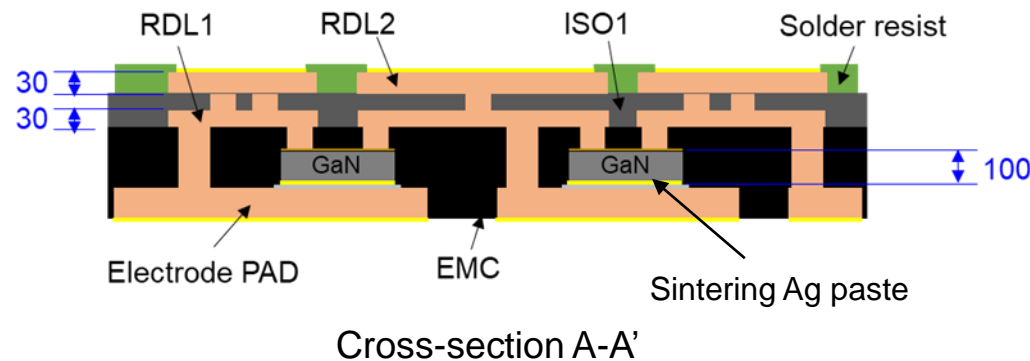
## ✓ **IMAPS DPC2023**

DC-DC half-bridge application (GaN HEMT module)  
Extreme Thin multi-chip module (350um)



X-ray CT 3D image

Package size : 7.5 × 7.0mm

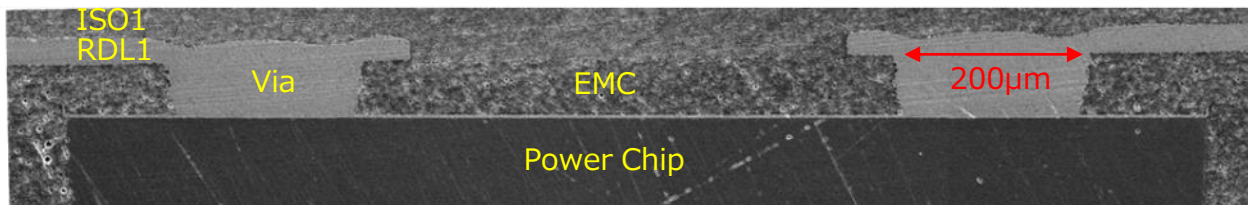


Cross-section A-A'

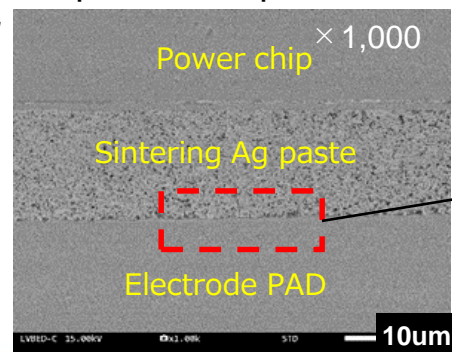
### Cross-section image



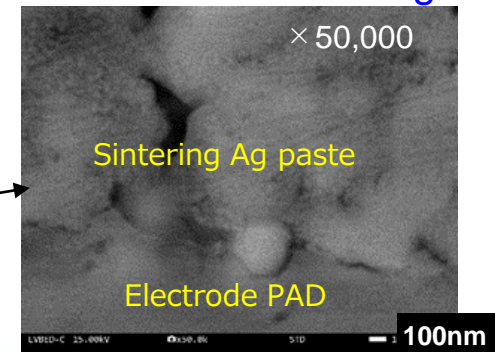
Direct Cu plating connection of power chips



Chip attached paste



Good Necking

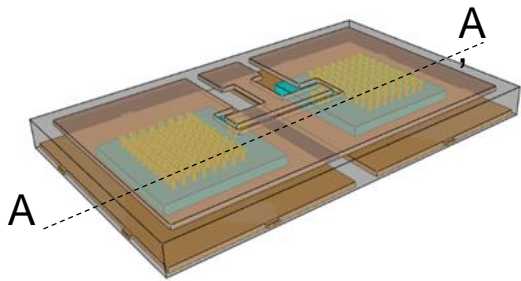


# Previous Technical Developments

## ✓ **IMAPS DPC2024**

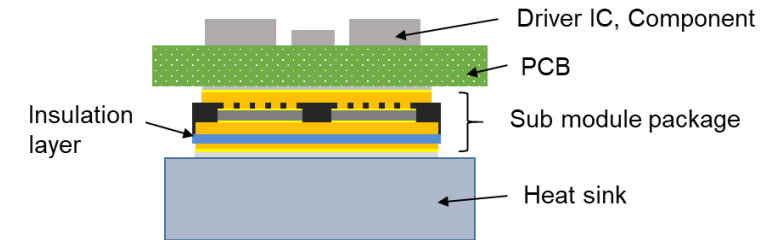
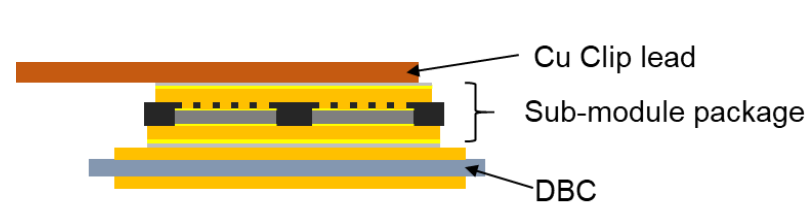
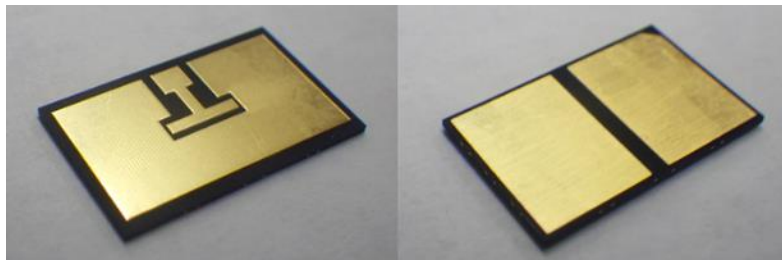
*SiC Sub-module  
for Inverter application*

Package size :16 × 10mm



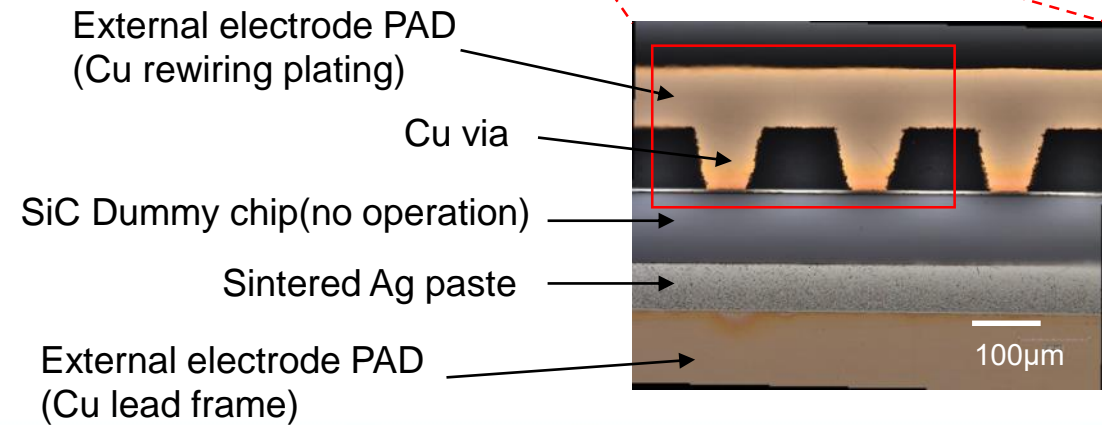
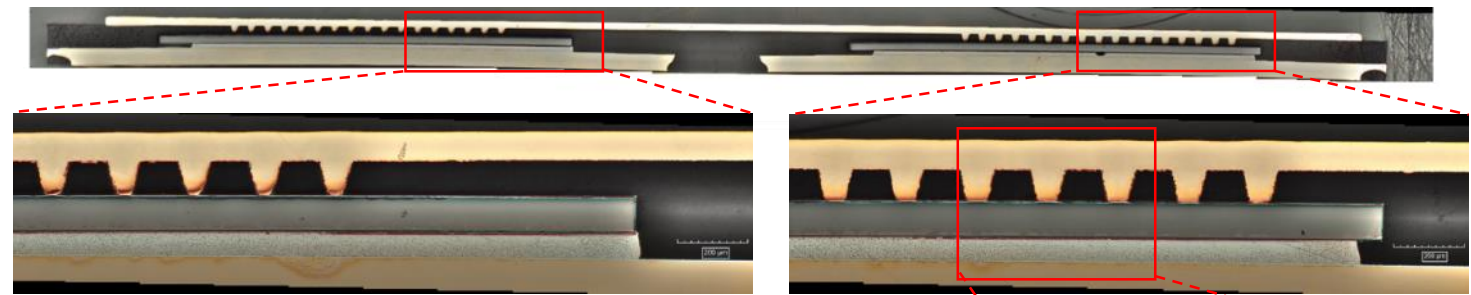
Top

Bottom



**Cross-section image**

**Very low resistance and inductance structure**

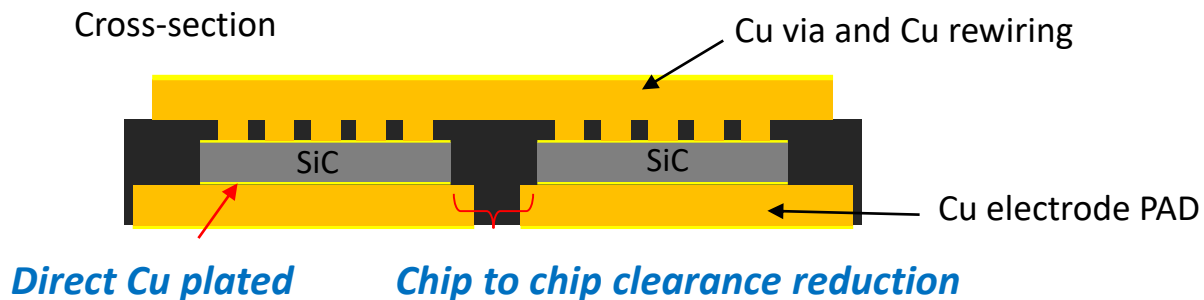


# Previous Technical Developments

## ✓ **IMAPS Power Electronics2024**

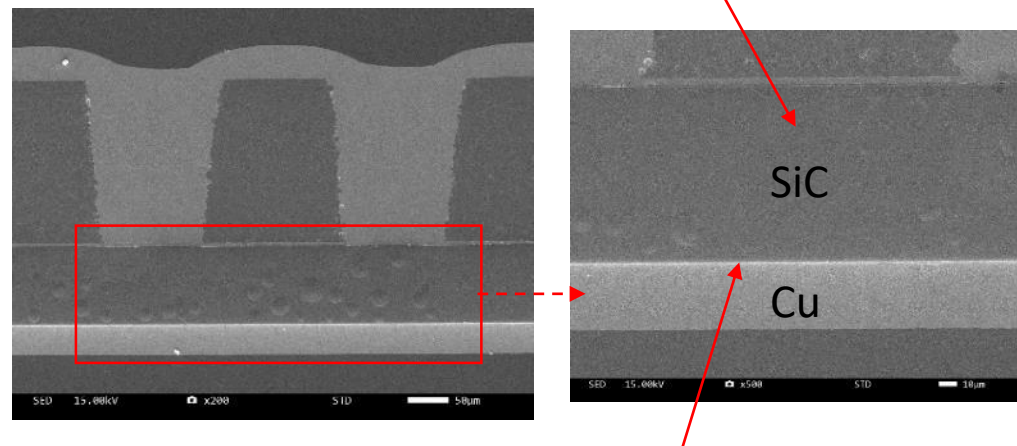
*SiC Sub-module for Inverter application*

### ✓ **SiC chip Direct Cu plated**



SiC Dummy chip(no operation)

Cross-section SEM image



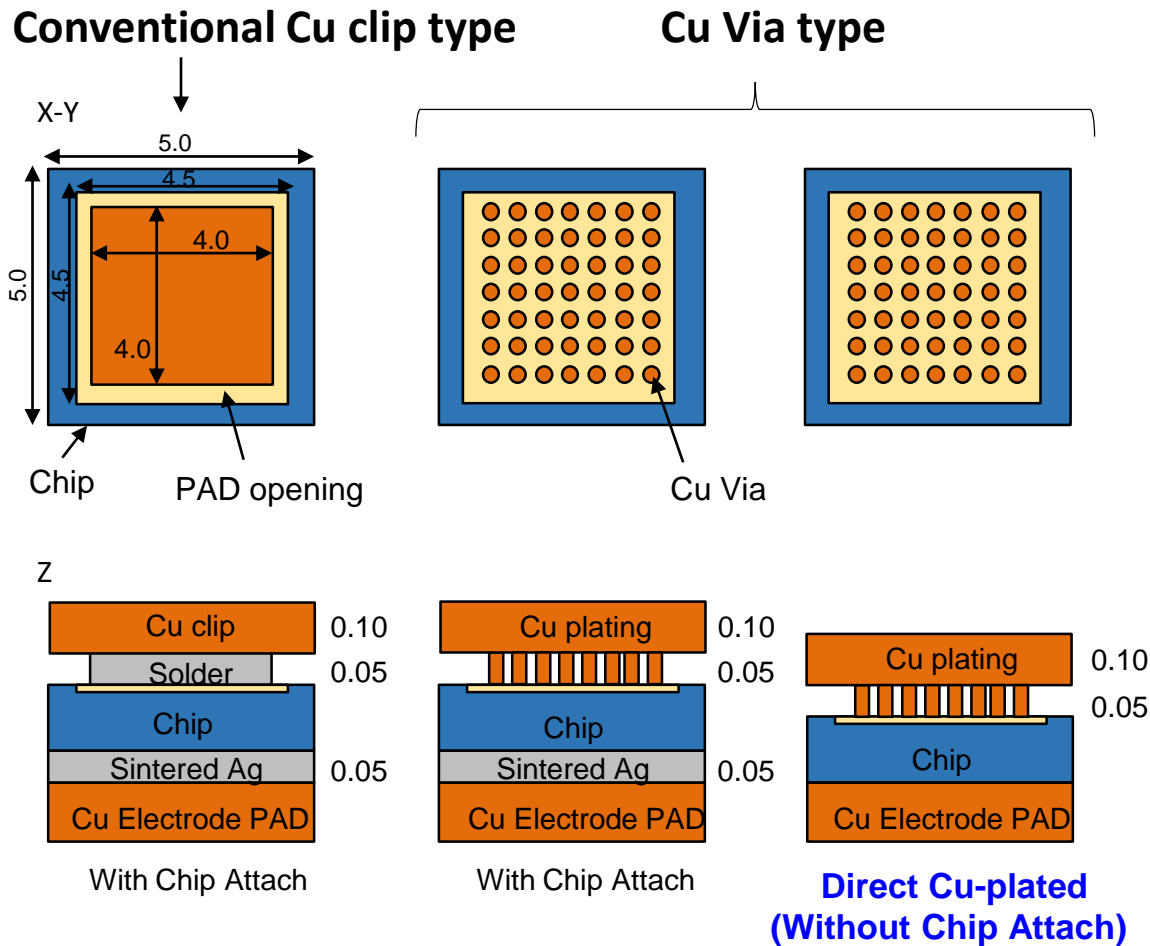
*Chip direct Cu plated  
(No bonding material)*

### <Motivations>

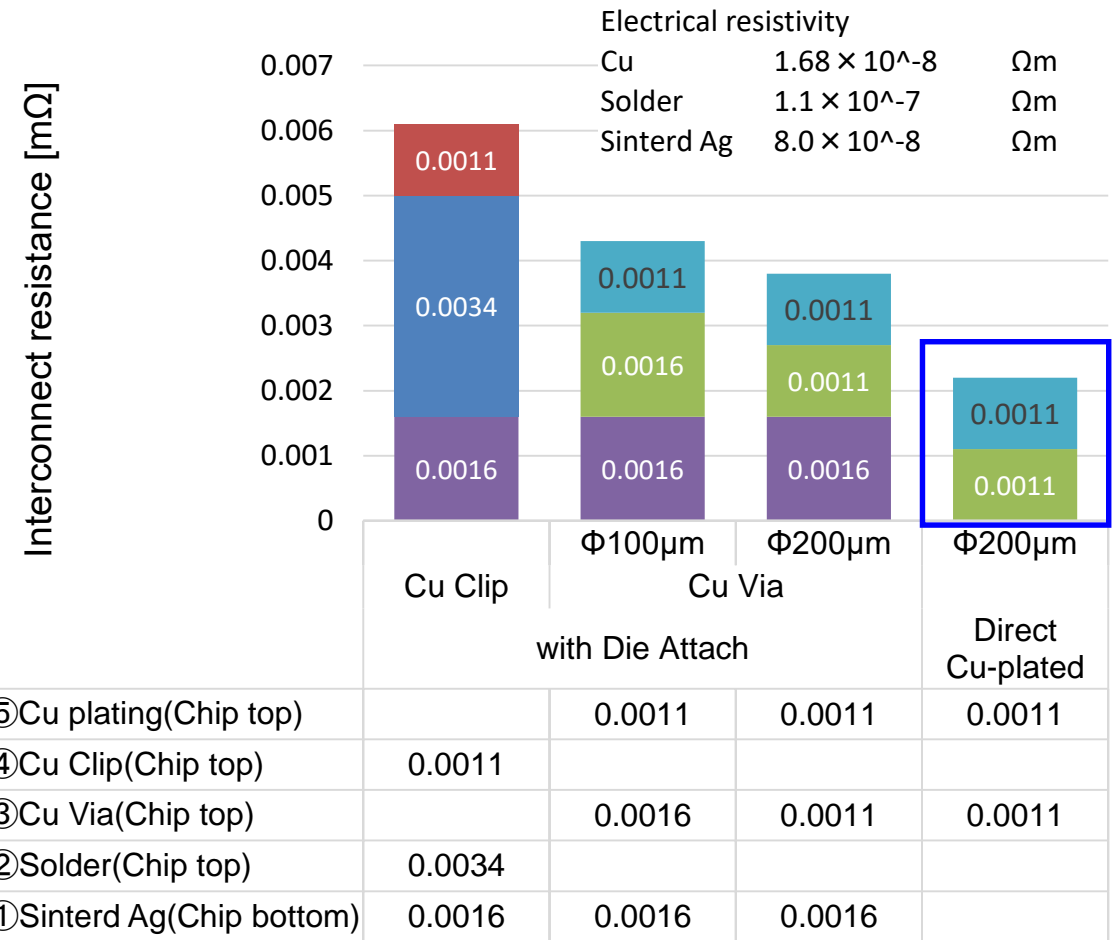
- **Lower resistance and higher heat dissipation**
- High Reliability Bonding with power chips
- No need for high temperature bonding process (reduced Cu surface oxidation)
- **Miniaturization through chip-to-chip clearance reduction**
- **Improved BLT, spread, fillet and void control issues (without die attach materials)**

# Previous Technical Developments

✓ **Advantages of direct Cu plated: Low resistance characteristics (theoretical calculation)**



Unit : mm



Chip and Cu Electrode PAD are not included.

# Previous Technical Developments

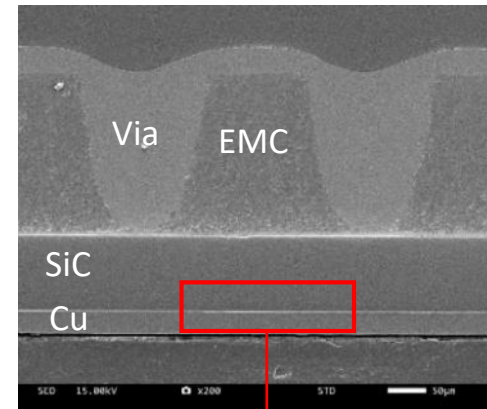
## ✓ TCT results for Direct Cu plated

Reliability test conditions (CLR: Component Level Reliability)

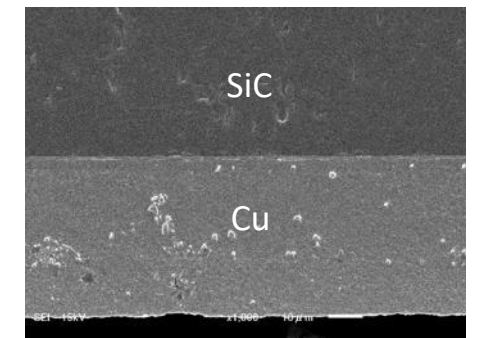
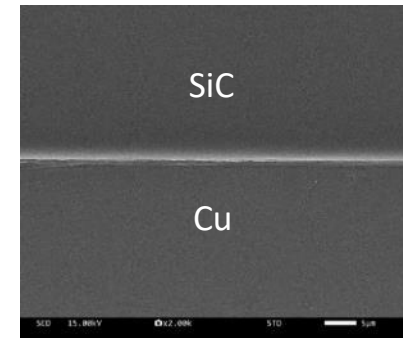
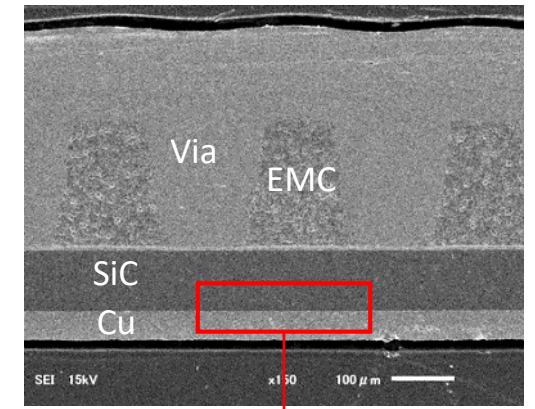
Test Items	Condition
Pre-Condition	The baking condition is 125 °C 24h. MSL = LEVEL1 Ta=85°C, RH=85%, storage=168h Reflow soldering heat stress (3times)
Thermal Cycle Test (TCT)	Ta= -65°C ⇄ 150°C

Cross-sectional SEM after each cycle

After 100cyc



After 300cyc



## Reliability test results

TCT	n=22	Time	100 cycles	300 cycles	500 cycles	1,000 cycles
		Result (Failure rate)	0/3	0/3	0/3	0/3

※Result :Cross-sectional SEM check by sampling

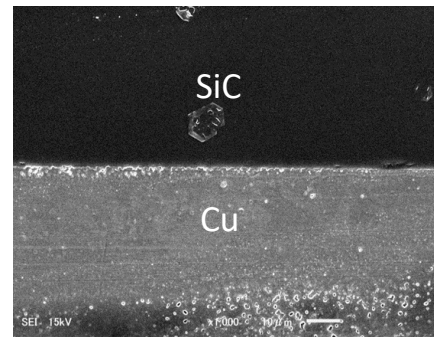
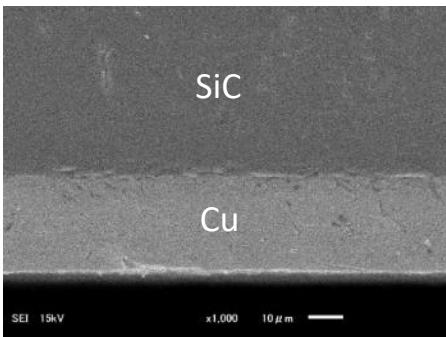
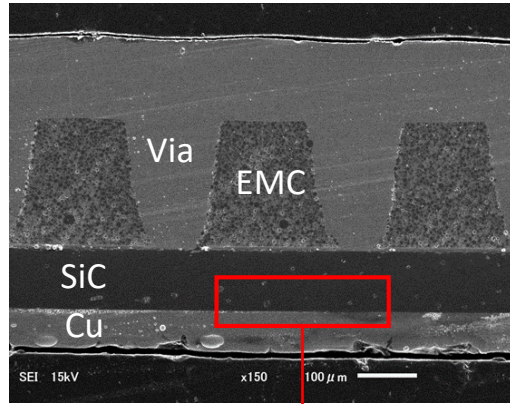
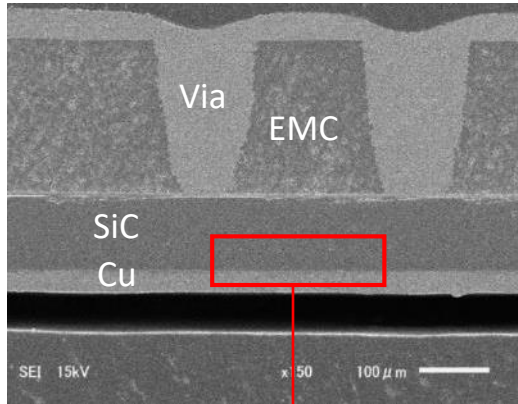
**No delamination and cracking**

# Previous Technical Developments

## ✓ TCT results for Direct Cu plated

After 500cyc

After 1,000cyc

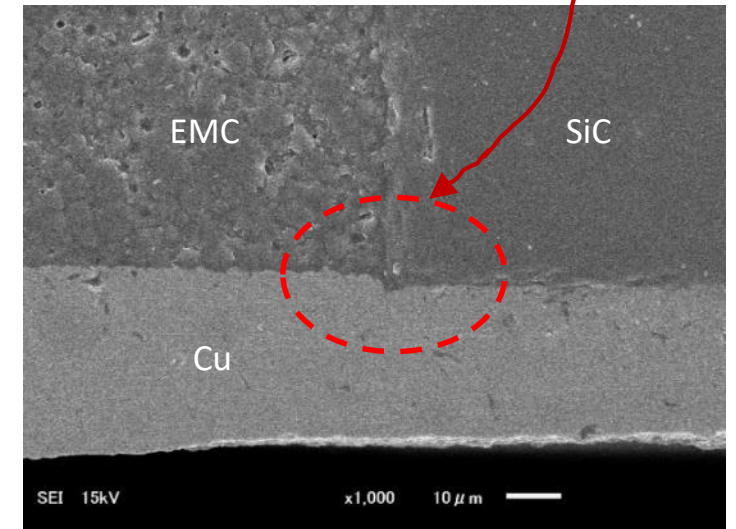
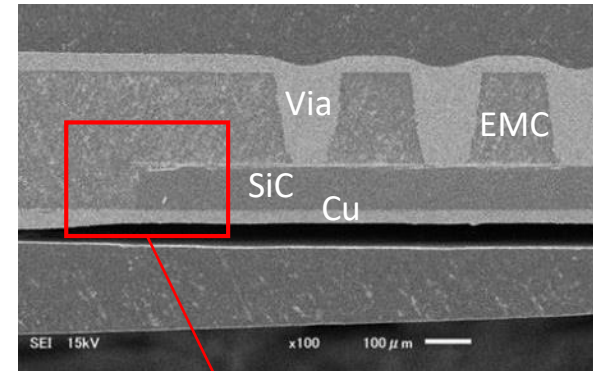


**No delamination and cracking**

More details analysis

Cross-sectional SEM after TCT 500cyc;

**SiC chip-edge position (Highest stress area)**



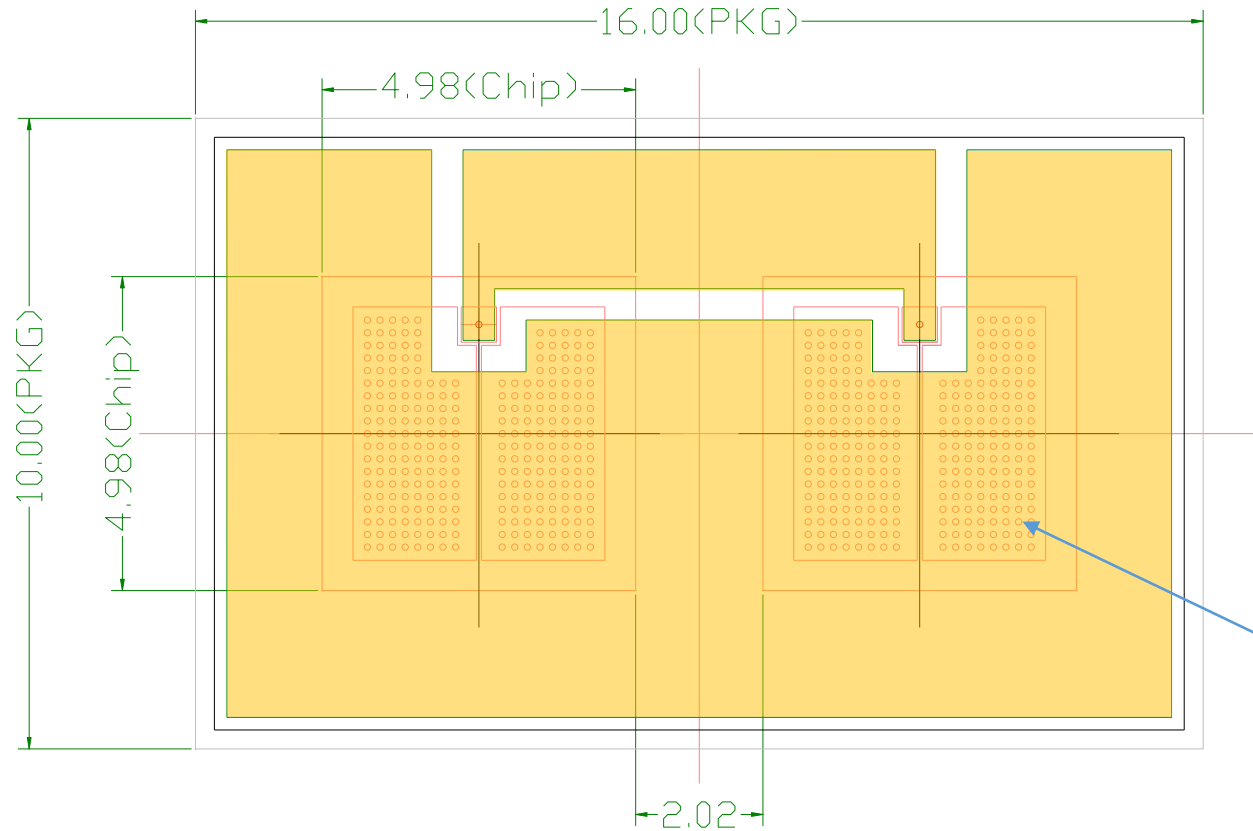
**No delamination and cracking**

# **Newly Updated Our Technical Developments**

## **Power Cycling Tests for direct Cu plated interconnect**

# Prototyping

## ✓ Package design



**Si – IGBT**  
**650V, 45A**

**Chip size**  
**4.98 × 4.98mm**

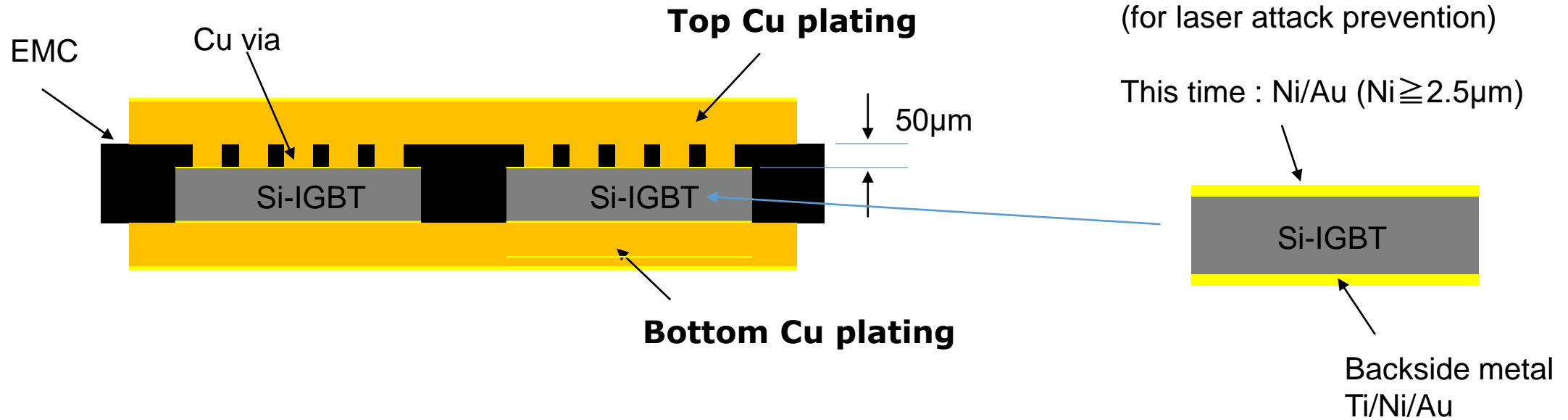
**Chip thickness**  
**90μm**

**2 chips in parallel**

**Via diameter 100μm**

# Prototyping

## ✓ Package vertical structure and dimensions



Level No.	Cu plating thickness(µm)	
	Top Cu	Bottom Cu
A	100	100
B	200	200

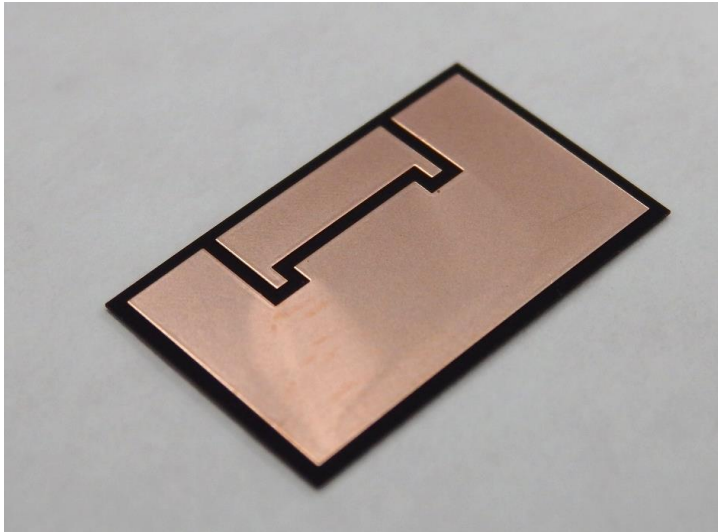
✳️ Trial level

# Prototyping

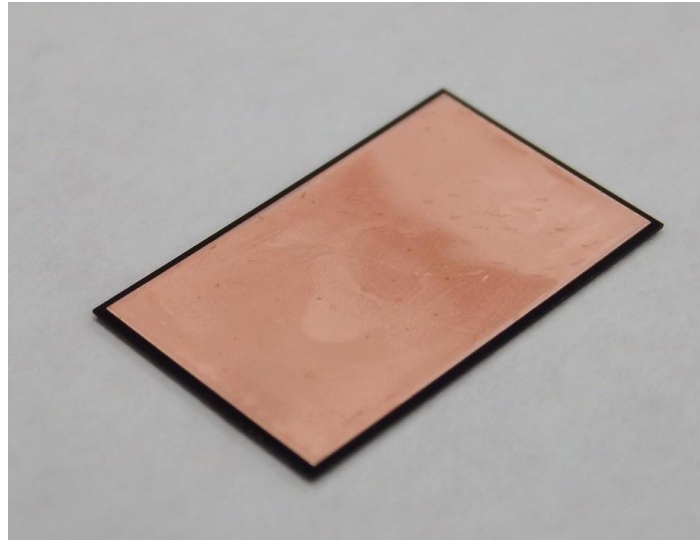
## ✓ *Finished Prototype*

### *Package external image*

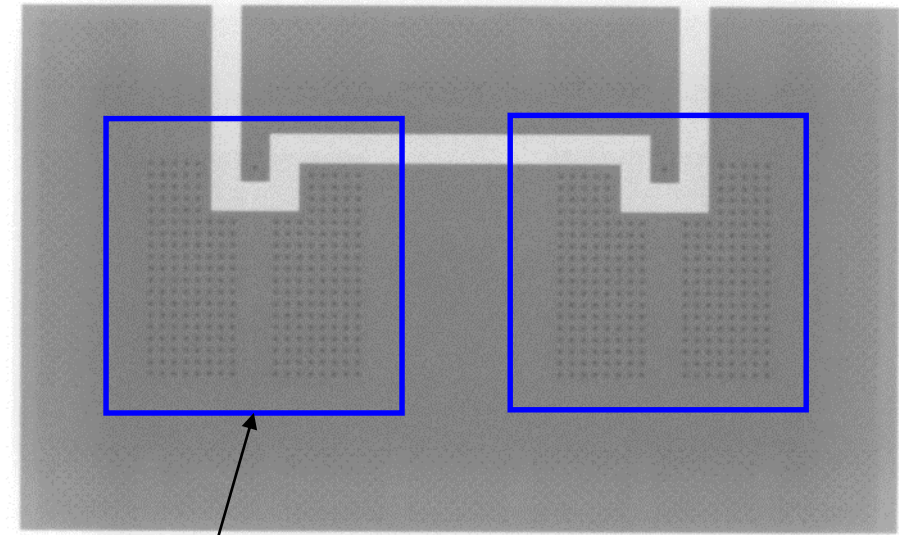
Top



Bottom



### *X-ray image*

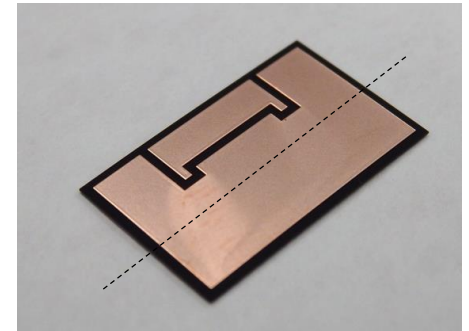
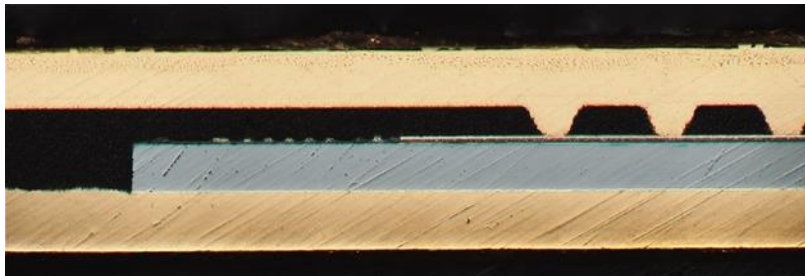


IGBT chip

# Prototyping

✓ **Finished Prototype**

**Cross-section image by microscope**

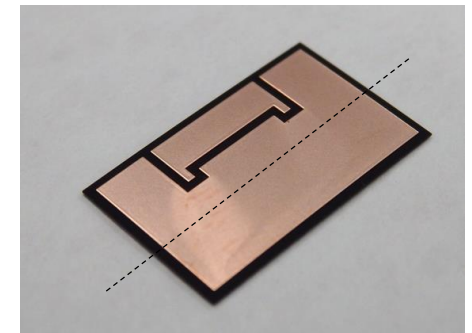


Level No.	Cu plating thickness(μm)	
	Top Cu	Bottom Cu
A	100	100

# Prototyping

✓ **Finished Prototype**

**Cross-section image by microscope**

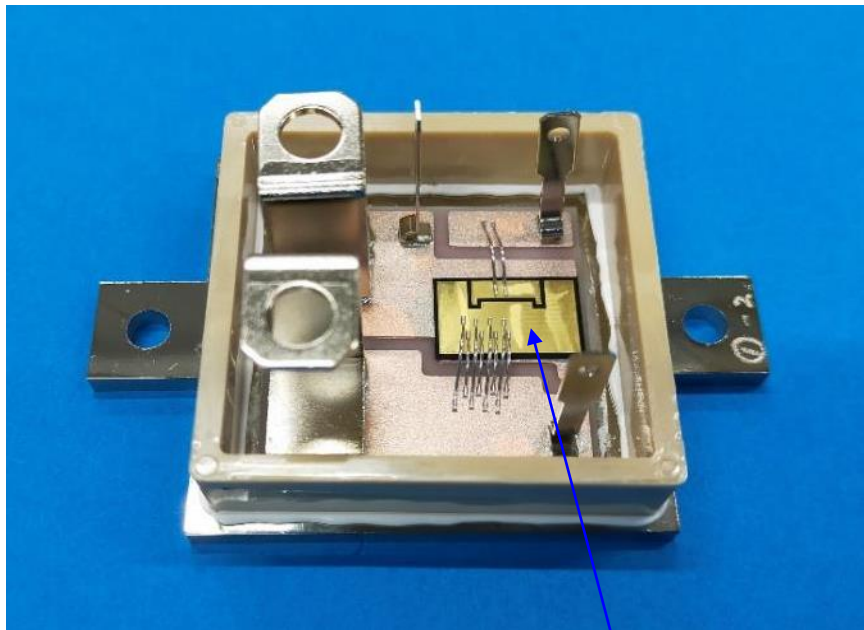


Level No.	Cu plating thickness(μm)	
	Top Cu	Bottom Cu
B	200	200

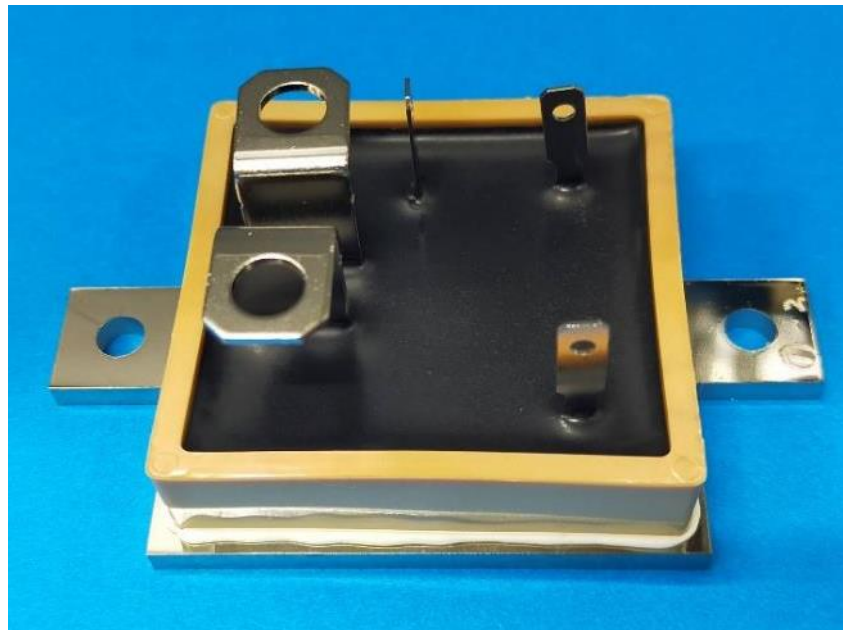
# Power Cycling Test

## ✓ *Power cycling test sample*

Before resin sealing

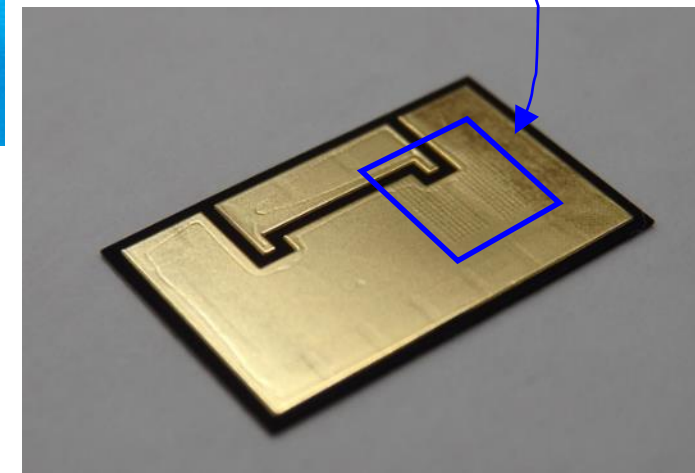


After resin sealing



Our sub-module in power module housing

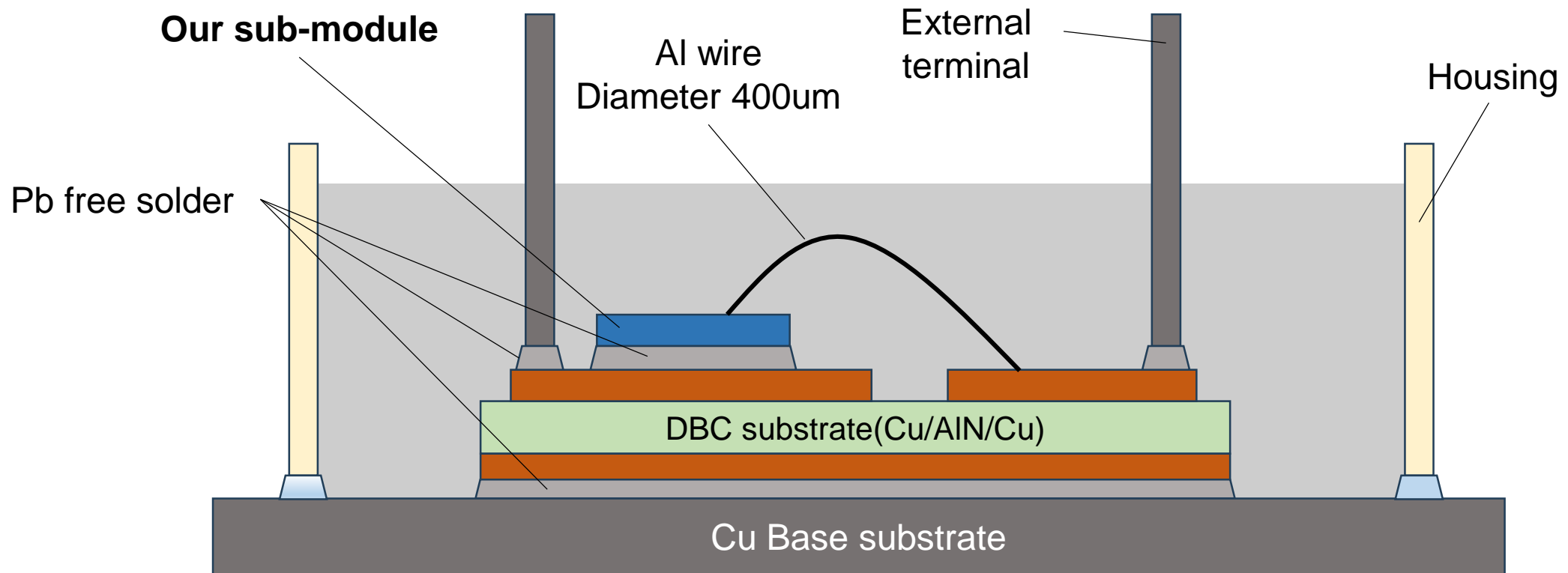
Using 1-chip sample



# Power Cycling Test

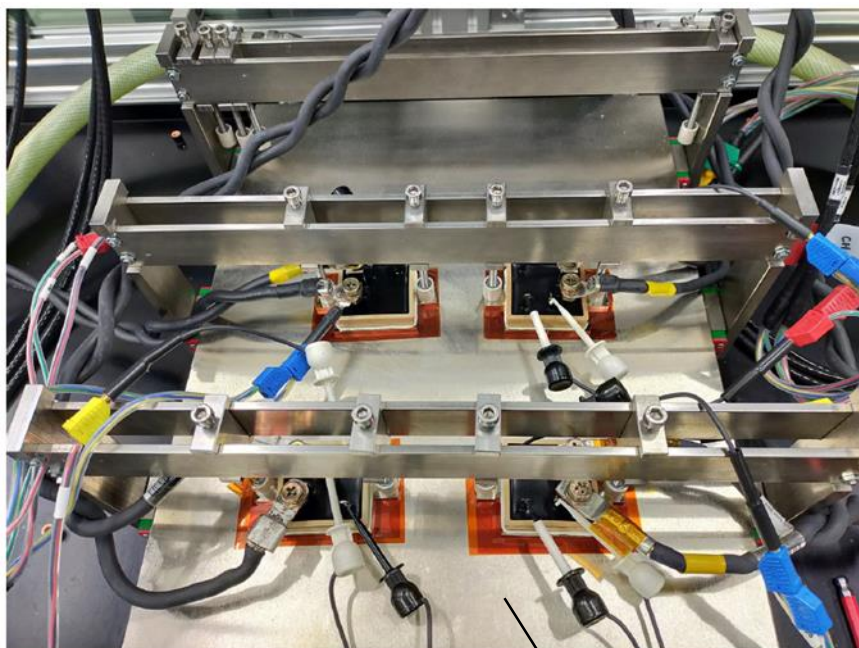
✓ **Power cycling test sample**

## Cross-section structure



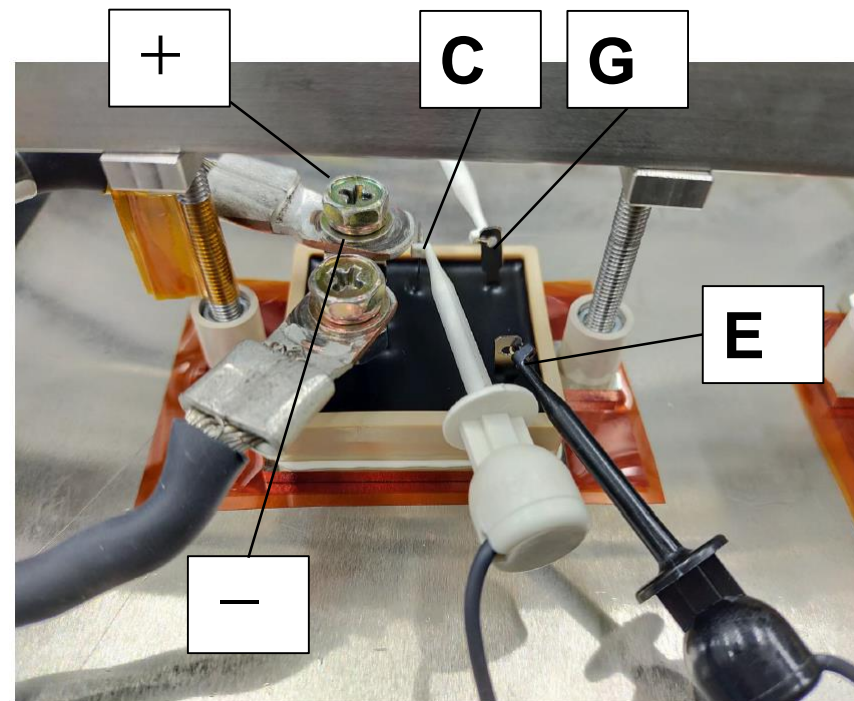
# Power Cycling Test

## ✓ Power cycling test setup



Cold plate

Outsourcing is used for testing (Chemitox, Japan)



- + : Input current
- : Output current
- C : Collector
- E : Emitter
- G : Gate

# Power Cycling Test

## ✓ **Test conditions**

Items	Conditions
Test mode	Current constant mode : 45A(Between C-E terminal)
Cold plate temperature	25°C
Number of Si-IGBT chips	1 chip
$\Delta T_j$	A sample : 75°C B sample : 65°C
ON/OFF time	ON=10sec OFF=20sec
Number of cycles	13,000 cyc

# Power Cycling Test

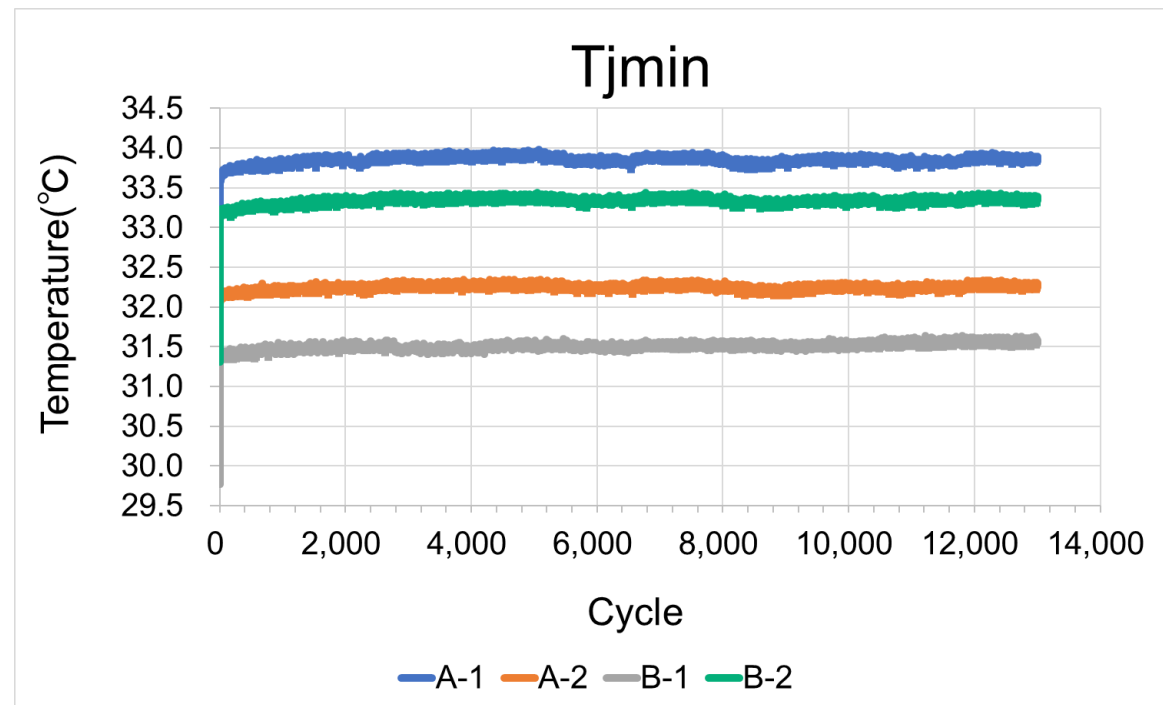
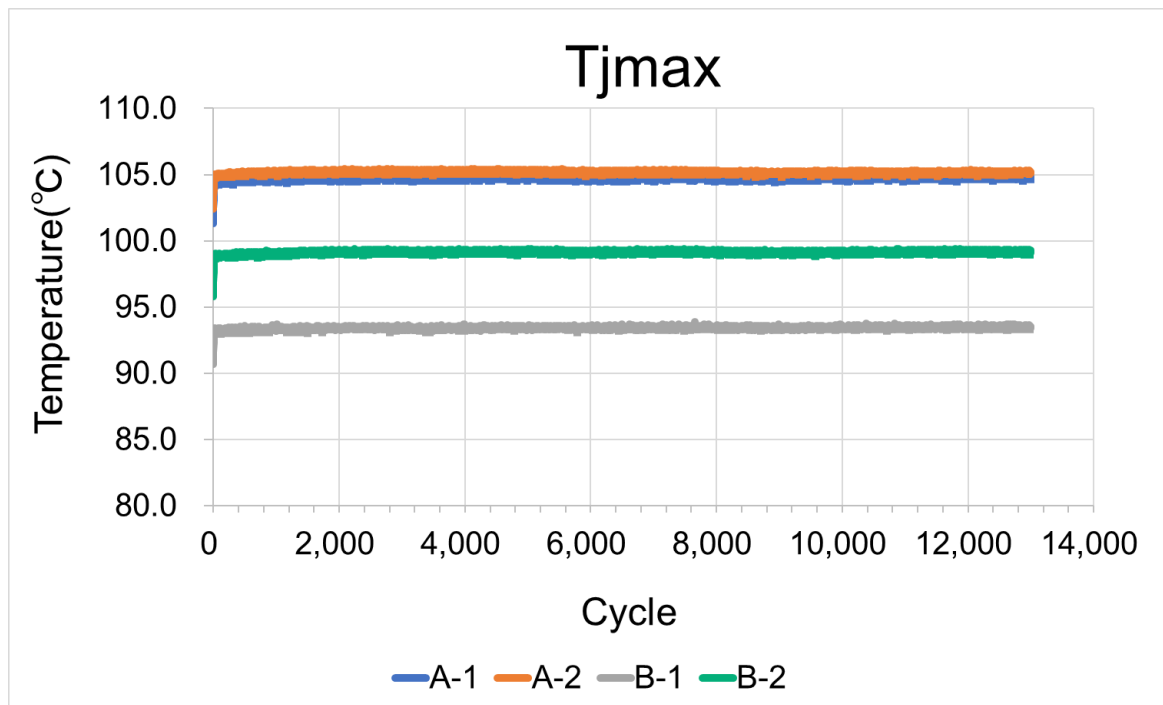
## ✓ *Judgment items*

Items	Remarks(means)
Tjmax	Maximum temperature of chip when ON
Tjmin	Minimum temperature of chip when OFF
$\Delta T_j$	Tjmax-Tjmin
Von	On-voltage at input current(45A)

# Power Cycling Test

✓ **Power cycling test results**

Sample A: Cu thickness 100µm  
 Sample B: Cu thickness 200µm



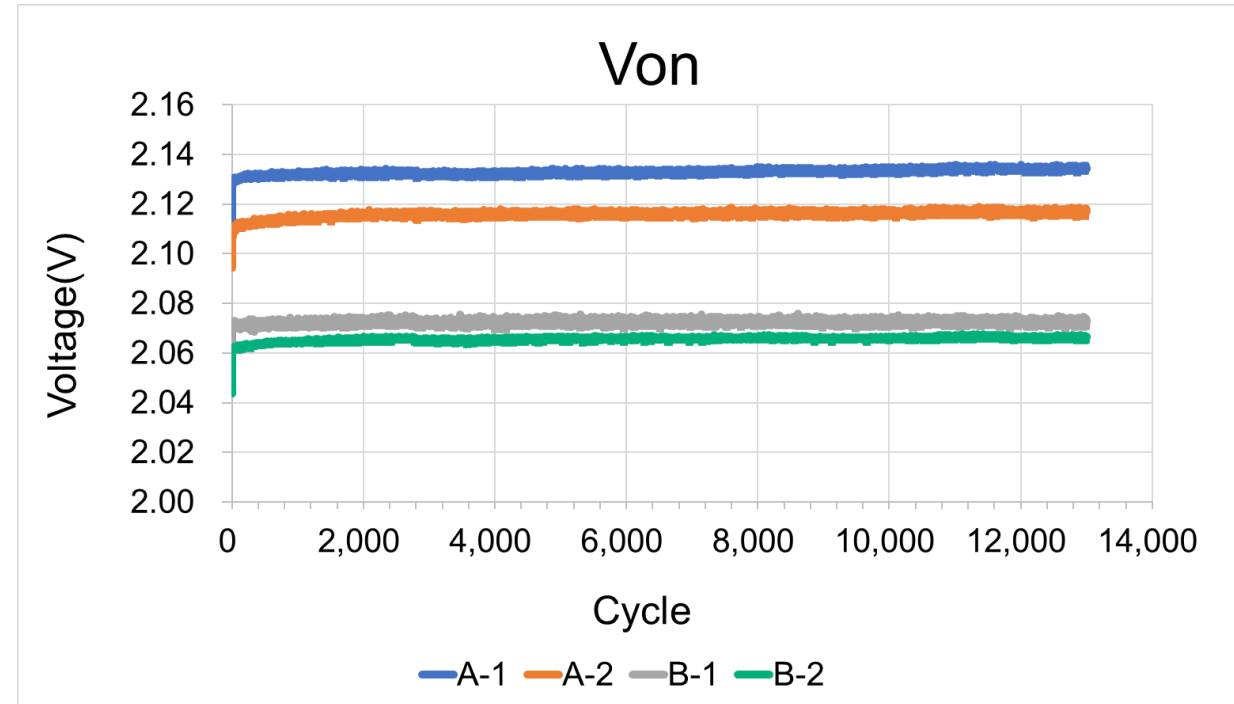
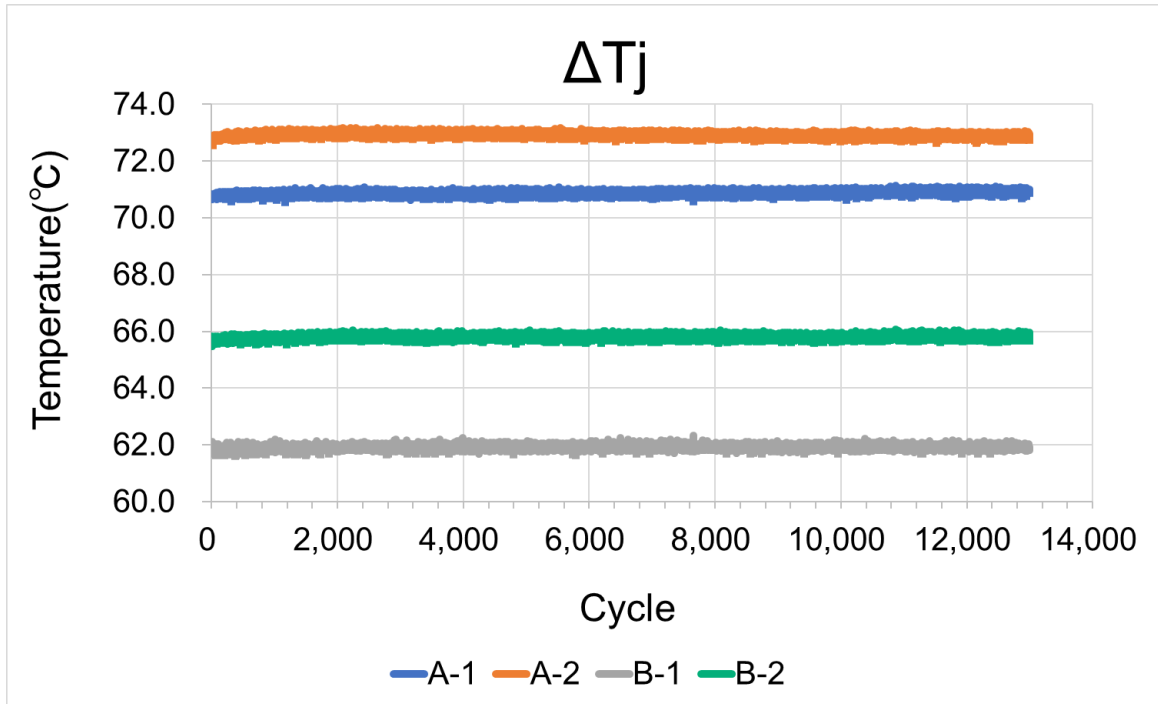
No characteristic change after 13,000 cycles

Good results

# Power Cycling Test

✓ **Power cycling test results**

Sample A: Cu thickness 100µm  
 Sample B: Cu thickness 200µm



No characteristic change after 13,000 cycles

Good results

# Summary

- ✓ We performed power cycling tests on Cu direct plated interconnections fabricated by a fan-out panel-level process.
- ✓ In this study, we examined the effect on connection reliability of different Cu thicknesses on the top and bottom of the chip.
- ✓ As a result of the power cycling test, we obtained good results with no change in any of the characteristics such as  $T_{jmax}$ ,  $T_{jmin}$  and  $V_{on}$ .
- ✓ In this study, we have obtained the possibility of direct connection with thick Cu to power chips.  
(100 $\mu$ m and 200 $\mu$ m thick Cu)
- ✓ As a next step, we plan to perform power cycling tests under higher current conditions (2-chip parallel Si-IGBTs).
- ✓ We also would like to evaluate TCT reliability testing at the board level(BLR).

Thank you for your attention.